

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	5547	(polysilicon same oxide same (CMP polish\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2006/11/04 16:43
L2	5527	1 and (wafer substrate)	US-PGPU B; USPAT; USOCR	OR	ON	2006/11/04 16:44
L3	877	2 and slurry	US-PGPU B; USPAT; USOCR	OR	ON	2006/11/04 16:44
L5	944	(polysilicon and oxide and (CMP polish\$3))	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/11/04 16:44
L6	843	5 and (wafer substrate)	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/11/04 16:47
L7	50	6 and slurry	FPRS; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/11/04 16:44